

A METHOD OF IMPROVING THE UNIFORMITY OF ETCHING OF A FILM ON
AN ARTICLE

ABSTRACT OF THE DISCLOSURE

5 A method of improving the uniformity of etching of a
film on an article, the method including the steps of
immersing the article containing the film into a tank of
etchant, rotating the article while in the etchant for a
desired amount of time so as to cause improved uniformity of
etching of the film compared to etching without rotating the
10 article, and removing the article from the tank of etchant.
In a preferred embodiment of the invention, the article is a
semiconductor wafer.